AMENDMENTS TO THE CLAIMS

The following listing of claims replaces all previous listings of claims in this application.

1. (Currently amended) A method for detecting a particle on a substrate, wherein the substrate is used in the fabrication of an integrated device, the method comprising:

contacting the integrated-device substrate with a monomer, wherein [[the]] a particle that catalyzes the polymerization of the monomer is disposed on the substrate, and

detecting the particle using a particle counter.

2. (Original) The method of claim 1, wherein the particle counter detects a property selected from the group consisting of number of particles, sizes of the particles, positions of the particles, and combinations thereof.

3. (Original) The method of claim 1, wherein the particle counter is capable of detecting particles on both sides of the substrate without unmounting the substrate.

4. (Original) The method of claim 1, wherein the particle counter detects particles optically.

5. (Previously presented) The method of claim 4, wherein the particle counter is a laser scanner.

6. (Original) The method of claim 4, wherein the particle counter detects a property selected from the group consisting of absorbance, fluorescence, reflectance, refractive index, and polarization.

7. (Currently amended) The method of claim 1, wherein [[the]] a composition of the particle is identified.

8. (Original) The method of claim 7, wherein the composition of the particle is identified by the polymerization rate of the monomer.

9. (Original) The method of claim 8, wherein the monomer is polymerized by a plurality of particle types.

10. (Original) The method of claim 8, further comprising repeating the contacting and detecting steps.

11. (Original) The method of claim 1, wherein the substrate is contacted with a plurality of monomers.

12. (Currently amended) The method of claim 11, wherein [[a]] the plurality of monomers contact the substrate simultaneously.

13. (Currently amended) The method of claim 11, wherein [[a]] the plurality of monomers contact the substrate sequentially.

14. (Original) The method of claim 1, wherein the particle is a metal.

15. (Original) The method of claim 14, wherein the metal is copper.

16. (Original) The method of claim 1, wherein the substrate comprises silicon.

17. (Original) The method of claim 16, wherein the substrate comprises a single crystal silicon wafer.

18. (Currently amended) The method of claim 1, wherein the monomer is in [[the]] a vapor phase.

19. (Original) The method of claim 1, wherein the monomer is an alkene.

20. (Original) The method of claim 19, wherein the alkene is selected from the group consisting of styrene, methyl acrylate, ethyl acrylate, methyl methacrylate, and acrylonitrile.

21. (Original) The method of claim 1, wherein the monomer is selected from the group consisting of aniline and thiophene.

22. (Original) The method of claim 1, further comprising an initiator.

23. (Original) The method of claim 22, wherein the initiator is benzyl bromide.

24. (Original) The method of claim 1, wherein the substrate is irradiated with electromagnetic radiation.

25–51. (Canceled)